

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

Γ	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
	10/810,659	03/29/2004	Soon-Sung Yoo	8733.341.10-US	1134	
	30827 7590 11/23/2005			EXAMINER		
		MCKENNA LONG & ALDRIDGE LLP 1900 K STREET, NW			KIM, RICHARD H	
		N, DC 20006		ART UNIT	PAPER NUMBER	
		•		2871		

DATE MAILED: 11/23/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	(K				
	Application No.	Applicant(s)			
	10/810,659	YOO ET AL.			
Office Action Summary	Examiner	Art Unit			
	Richard H. Kim	2871			
The MAILING DATE of this communication apperiod for Reply	ppears on the cover sheet	with the correspondence address			
A SHORTENED STATUTORY PERIOD FOR REP WHICHEVER IS LONGER, FROM THE MAILING I Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory perior Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUI .136(a). In no event, however, may d will apply and will expire SIX (6) M tte, cause the application to become	NICATION. a reply be timely filed ONTHS from the mailing date of this communication. ABANDONED (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 17.	<u>August 2005</u> .				
2a)⊠ This action is FINAL . 2b)□ Th	This action is FINAL. 2b) This action is non-final.				
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice under	Ex parte Quayle, 1935 C	.D. 11, 453 O.G. 213.			
Disposition of Claims					
4)	awn from consideration.				
Application Papers					
9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) ac Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	cepted or b) objected to drawing(s) be held in abey ction is required if the drawing	ance. See 37 CFR 1.85(a). ng(s) is objected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.					
Attachment(s)	о П., .	0 (070 110)			
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date	Paper No	Summary (PTO-413) o(s)/Mail Date Informal Patent Application (PTO-152) 			

Application/Control Number: 10/810,659

Art Unit: 2871

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 19 and 20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wook (US 5,894,136) in view of Kim (US 6,043,511).

Wook discloses an array substrate for an active matrix type liquid crystal display device comprising a substrate (Fig. 6F, ref. 1); a gate line of the substrate, wherein the gate line includes a gate pad (Fig. 6F, ref. 4, col. 1, lines 49); a first insulating layer on the gate line and the substrate (6); a semiconductor layer on the first insulating layer and over a portion of the gate line (7); a date line over the first insulating layer and that crosses the gate line (9), the data line including a protruding portion that projects in a direction of the semiconductor layer and that forms a source electrode (9a), wherein an end portion of the semiconductor layer under the data line coincides to an end portion of the data line (col. 4, lines 44-47), wherein the data line further includes a data pad (col. 1, line 50); a drain electrode spaced apart from the source electrode and extending in a rectangular region partially defined by the gate and data lines (9b); a passivation layer on the drain electrode, the passivation layer having a drain contact hole that exposes the drain electrode (10); and a pixel electrode formed over the passivation layer, the pixel electrode electrically connecting to the drain electrode vial the drain contact hole (11). However, the reference does not disclose the device wherein the pixel electrode extends over a portion of the

Art Unit: 2871

gate line so as to form a storage capacitor comprised of the pixel electrode, the gate line, and the first insulating layer, wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line, wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line that includes a semiconductor layer and the passivation layer.

Kim discloses a device wherein the pixel electrode extends over a portion of the gate line so as to form a storage capacitor (Fig. 10) comprised of the pixel electrode (70), the gate line (111), and the first insulating layer (20), wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line, wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line that includes a semiconductor layer (30) and the passivation layer (20).

It would have been obvious to one having ordinary skill in the art at the time the invention was made for the pixel electrode to extend over a portion of the gate line so as to form a storage capacitor comprised of the pixel electrode, the gate line, and the first insulating layer, wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line, wherein the storage capacitor further includes a short-preventing part disposed between the pixel electrode and the gate line that includes a semiconductor layer and the passivation layer since one would be motivated to produce a display of high picture quality by providing a capacitor which would prevent leaking out of a signal before a second signal is applied.

Art Unit: 2871

3. Claim 21 is rejected under 35 U.S.C. 103(a) as being unpatentable over Wook and Kim in view of Han et al. (US 5,926,235).

Wook and Kim disclose the device previously recited, but fails to disclose that the shortpreventing part further includes an ohmic contact layer, and a conducting material between the semiconductor layer and the passivation layer.

Han et al. discloses a device wherein the short-preventing part includes an ohmic contact layer (112), and a conducting material between the semiconductor layer and the passivation layer (130).

It would have been obvious to one having ordinary skill in the art at the time the invention was made to employ an ohmic contact layer, and a conducting material between the semiconductor layer and the passivation layer since one would be motivated to reduce the number of masks used in the fabrication process (col. 2, lines 40-42).

Response to Arguments

- 4. Applicant's arguments filed 8/17/05 have been fully considered but they are not persuasive.
- 5. In arguing that Wook does not disclose "an end portion of the semiconductor layer under the data line coincides to an end portion of the data line", Applicant argues that since Wook discloses a LCD in which "the high concentration n-type amorphous silicon layer 8 and amorphous silicon layer 7 under the data line are formed wider than the data line", the end portion of the semiconductor layer under the data line do not coincide with an end portion of the data line. However, Examiner respectfully disagrees. The dictionary defines "coincide" as "to occupy the same relative position or the same area in space." In Wook, even though the silicon

Art Unit: 2871

layer is wider than the data line, both the end portion of the silicon layer and the end portion of the data line occupy a same space, namely the space defined by the end portion of the data line.

Therefore, it can be concluded that an end portion of the semiconductor layer under the data line does indeed coincides to an end portion of the data line.

Conclusion

6. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Richard H. Kim whose telephone number is (571)272-2294. The examiner can normally be reached on 9:00-6:30 M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robert H. Kim can be reached on (571)272-2293. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Application/Control Number: 10/810,659

Art Unit: 2871

Application Information Retrieval (PAIR) system. Status information for published applications

Information regarding the status of an application may be obtained from the Patent

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Richard H Kim Examiner Art Unit 2871

RHK

ANDREW SCHECHTER
PRIMARY EXAMINER

Page 6